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Substitute for form 1449A/PTO INFORMATION DISCLOSURE	Complete if Known			
STATEMENT BY APPLICANT	Application Number	10/721585		
Use as many sheets as necessary)	Filing Date	November 25, 2003		
O 1 P & CO	First Named Inventor	Forbes, Leonard		
	Group Art Unit	2825		
	Examiner Name	Unknown C. Everhant		
Sheet 1 of No.	Attorney Docket No: 1	1303.017US2		

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT	Application Number	Unknown 10/721,585		
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	First Named Inventor	Forbes, Leonard		
	Group Art Unit	Unknown 2825		
	Examiner Name	Unknown C. Evenhart		
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INFORMATION DISCLOSURE STATEMENT BY APPLICANT	Application Number	Unknown 10/721,585		
(Use as many sheets as necessary)	Filing Date	Even Date Herewith 11/25/03		
	First Named Inventor	Forbes, Leonard		
	Group Art Unit	Unknown 2826		
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